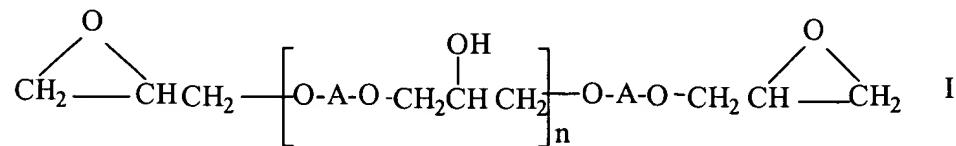


[Phillips-1]

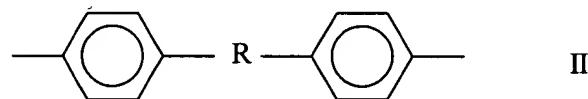
Amendments to the Claims:

The following claims will replace all prior versions of the claims in this application (in the unlikely event that no claims follow herein, the previously pending claims will remain):

1. (Currently amended) An ultraviolet light curable resin composition comprising [a water soluble] an aqueous solution of an amine salt prepolymer formed by reaction in an aqueous mixture between an unsaturated carboxylic acid and an oligomer having at least one amine group selected from the group consisting of urea formaldehyde resins, melamine formaldehyde resins, amine-polyisocyanate adducts, Michael adducts of a secondary amine and acrylate and/or methacrylate compounds and epoxy-amine adducts formed between [an] a secondary amine and epoxy of formula:



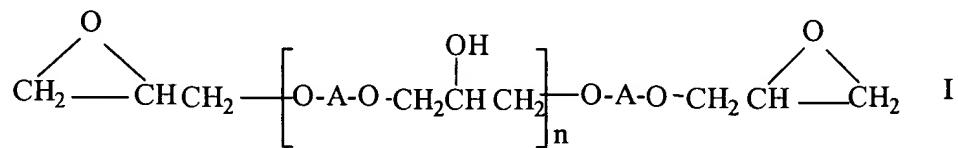
wherein n is from 0 to 10 and A comprises a diradical selected from the group consisting of aromatic, substituted aromatic and the diradical of formula II:



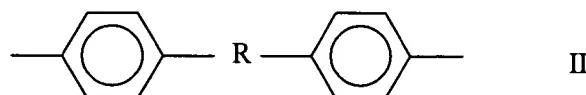
wherein R is an alkylene group of 1 to 4 carbon atoms.

[Phillips-1]

2. (Previously presented) A resin composition according to claim 1 comprising an aqueous solution containing a weight ratio of amine salt prepolymer to water in the range of from 1:4 to 20:1.
3. (Previously presented) A resin composition according to claim 2 wherein said weight ratio is in the range of from 3:2 to 9:1.
4. (Previously presented) A resin composition according to claim 1 which is curable by UV and contains less than 0.5% by weight based on the weight of the resin component of a UV initiator.
5. (Previously presented) A resin composition according to claim 1 which is curable by UV in the absence of photoinitiator.
6. (Previously presented) A resin composition according to claim 1 wherein the oligomer having at least one amine group is an epoxy-amine formed between a secondary amine and an epoxide of formula I:



wherein n is from 0 to 10 and A is a diradical of formula II:

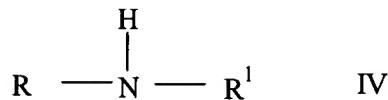


wherein R is an alkylene group of 1 to 4 carbon atoms.

7. (Previously presented) A resin composition according to claim 6 wherein the epoxide of formula I is a product of epichlorohydrin and bisphenol A.

8. (Previously presented) A resin composition according to claim 6, wherein the amine adduct is formed using a molar ratio of amine to epoxide compound in the range of from 0.5:1 to 2.05:1.
9. (Previously presented) A resin composition according to claim 6 wherein the molar ratio of amine to epoxide compound is 0.95:1 to 1.6:1.
10. (Previously presented) A resin composition according to claim 1 wherein the oligomer having at least one amine group is prepared from melamine, formaldehyde and/or glyoxal and optionally one or more alcohols selected from the group consisting of C₁ to C₆ alkanols, C₁ to C₆ alkyl ethers of C₁ to C₆ alkylene glycols and C₁ to C₆ alkylene glycols.
11. (Previously presented) A resin composition according to claim 1 wherein the oligomer having at least one amine group is a urethane-amine adduct prepared by reaction of a secondary amine with a polyisocyanate.
12. (Previously presented) A resin composition according to claim 1 wherein the urethane amine adduct is formed from a molar ratio of amine to polyisocyanate of from 0.90:1 to 1.6:1.
13. (Previously presented) A resin composition according to claim 1 wherein the oligomer having at least one amine group is a Michael adduct formed between a secondary amine and an unsaturated compound selected from the group consisting of monomers and prepolymers comprising a plurality of unsaturated groups including at least one acrylate or methacrylate group.
14. (Previously presented) A resin composition according to any one of claims 6 to 9 wherein the secondary amine is amine of formula IV:

[Phillips-1]



wherein R and R' are independently selected from straight and branched chain aliphatic of up to 6 carbon atoms optionally substituted by hydroxy and mixtures thereof.

15. (Previously presented) A resin composition according to claim 1 wherein the unsaturated acid is selected from the group consisting of acrylic acid, methacrylic acid, crotonic acid, citraconic acid, sorbic acid, fumaric acid and mixtures of two or more thereof.

16. (Previously presented) A resin according to claim 1 wherein the unsaturated acid is selected from the group consisting of acrylic acid and methacrylic acid.

17. (Deleted)

18. (Deleted)

19. (Deleted)

20. (Deleted)

21. (Previously presented) A method of forming a coating on a substrate comprising applying to the substrate a layer of an aqueous solution of a radiation curable resin according to claim 1 and subjecting the layer of said aqueous solution to ultraviolet radiation to cure the layer.

22. (Previously presented) The method according to claim 21 wherein the composition is applied at a thickness of up to 200 microns.

23. (New) A method according to claim 21 wherein the concentration of the radiation curable resin according to claim 1 is from 20 to 95% by weight of the total aqueous solution.